ABSTRACT OF THE DISCLOSURE

A photosensitive resist layer is formed on one surface of a single-polarized ferroelectric substance having nonlinear optical effects. The resist layer has properties such that, when light is irradiated to the resist layer, only exposed areas of the resist layer or only unexposed areas of the resist layer become soluble in a developing solvent. The resist layer is then exposed to near-field light in a periodic pattern with a device, which receives exposure light and produces the near-field light in the periodic pattern. The resist layer is then developed to form a periodic pattern. A periodic electrode is then formed on the one surface of the ferroelectric substance by utilizing the periodic pattern of the resist layer as a mask, the periodic electrode being formed at positions corresponding to opening areas of the mask. An electric field is applied across the ferroelectric substance by utilizing the periodic electrode to set regions of the ferroelectric substance, which stand facing the periodic electrode, as domain inversion regions.